

Docket No.: MUH-12757

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : MATTHIAS KROENKE ET AL.

Filed : CONCURRENTLY HEREWITH

Title : METHOD FOR FABRICATING FERROELECTRIC MEMORY CELLS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

U.S. Patent No. 5,536,672 (Miller et al.), dated July 16, 1996;

U.S. Patent No. 5,932,907 (Grill et al.), dated August 3, 1999;

German Published Non-Prosecuted Patent Application DE 100 14 315 A1 (Yamazaki et al.), dated October 5, 2000 and corresponding U.S. Patent Application Publication No. 2002/0185683 A1 (Yamazaki et al.), dated December 12, 2002;

PCT WO 00/39842 (Nagel et al.), dated July 6, 2000 and corresponding U.S. Patent Application Publication No. 2002/0070404 A1 (Bruchhaus et al.), dated June 13, 2002;

PCT WO 00/49660 (Joshi et al.), dated August 24, 2000;

PCT WO 99/28972 (Baumert et al.), dated June 10, 1999;

PCT WO 98/15012 (Hartner et al.), dated April 9, 1998;

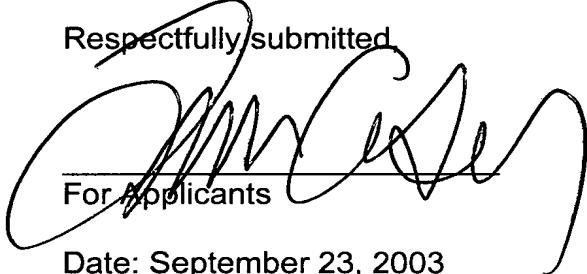
Heintze, M. et al.: "Oxygen Impurity Effects on the Formation of Thin Titanium Silicide Films by Rapid Thermal Annealing", J. Appl. Phys., Vol. 23, 1990, pp. 1076-1081;

Wee, A. et al.: "Investigation of Titanium Silicide Formation Using Secondary Ion Mass Spectrometry", Mat. Res. Soc. Symp. Proc., Vol. 342, April, 4 1994, pp. 117-122;

International Search Report, dated November 27, 2002.

If no translation of pertinent portions of any foreign language patents or publications mentioned above is included with the aforementioned copies of those applications, patents and/or publications, it is because no existing translation is readily available to the applicant.

Respectfully submitted,


For Applicants

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Date: September 23, 2003

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FORM PTO-1449 (SUBSTITUTE)				Attorney Docket No.: MUH-12757 Appl. No.:			
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE							
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))				Applicant: MATTHIAS KROENKE ET AL.			
				Filing Date: September 23, 2003 Group Art Unit:			

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
	A	5,536,672	7/16/96	Miller et al.			
	B	5,932,907	8/3/99	Grill et al.			
	C	2002/0185683 A1	12/12/02	Yamazaki et al.			
	D	2002/0070404 A1	6/13/02	Bruchhaus et al.			
	E						
	F						
	G						
	H						
	I						

FOREIGN PATENT DOCUMENT

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES NO
	J	100 14 315 A1	10/5/00	Germany			
	K	00/39842	7/6/00	WIPO			
	L	00/49660	8/24/00	WIPO			
	M	99/28972	6/10/99	WIPO			
	N	98/15012	4/9/98	WIPO			

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

	Heintze, M. et al.: "Oxygen Impurity Effects on the Formation of Thin Titanium Silicide Films by Rapid Thermal Annealing", J. Appl. Phys., Vol. 23, 1990, pp. 1076-1081;
	Wee, A. et al.: "Investigation of Titanium Silicide Formation Using Secondary Ion Mass Spectrometry", Mat. Res. Soc. Symp. Proc., Vol. 342, April, 4 1994, pp. 117-122

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.